

Face Polishing Scrub

25351



Phase	%	Tradename	INCI	Supplier	Function
A	50.0	ZEMEA	Propanediol	CovationBIO	Moisturization and much more
A	10.0	TEXTURLUX Feel	Hydroxypropyl Starch Phosphate	Primient	Clear gellant
A	5.0	GLYPURE 99	Glycolic Acid	PureTech Scientific	Fantastic exfoliant
B	25.0		Water		Solvent
C	10.0	SOLESPHERE NP-100	Silica	AGC	Polishing agent

Ingredients: Propanediol, Water, Hydroxypropyl Starch Phosphate, Silica, Glycolic Acid

Procedure

1. Premix A
2. Add B to A with sharp bladed impeller mixing
3. Add C to A/B and mix until uniform and smooth

Distinctives

- + 5% Glycolic Acid
 - o Featuring Glypure 99
- + High-moisturizing skin polishing gel
 - o ZEMEA moisture
 - o SOLESPHERE polish
- + Straightforward manufacturing
- + Beautiful clear gel
- + Leaves skin feeling soft and smooth